

Press Release

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Rutgers purchases Nanonex Advanced Nanoimprint Tool NX-B200

Princeton NJ, Apr. 25, 2008: Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the purchase of a Nanonex NX-B200 system by Rutgers, the State University of New Jersey, Piscataway, NJ.

The Nanonex NX-B200 purchased by the Institute for Advanced Materials, Devices, and Nanotechnology at Rutgers is a compact, cost-effective and versatile sub-10 nm resolution nanoimprint tool, utilizing Nanonex's patented Air Cushion Press™ technology to provide unsurpassed uniformity and yield over the entire substrate. The NX-B200 also incorporates a fully flexible Smart Sample Holder that accommodates any size of substrate or mask up to the maximum capability including arbitrary shaped geometries.

"Nanonex is pleased to have won the confidence of Rutgers University. The NX-B200 they have purchased will give them years of reliable service and enable the fine research they are undertaking." Larry Koecher, Chief Operating Officer of Nanonex.

About Nanonex Corporation

Nanonex is the inventor of "nanoimprint lithography", the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex's patented and proprietary nanoimprint lithography (NIL) solutions and Air-Cushion Press™ can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of industry applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of more than 40 tools world-wide. Visit www.nanonex.com for additional information.